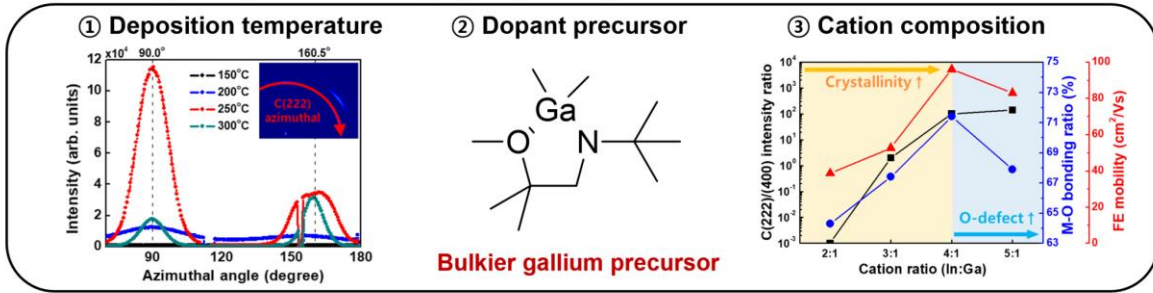
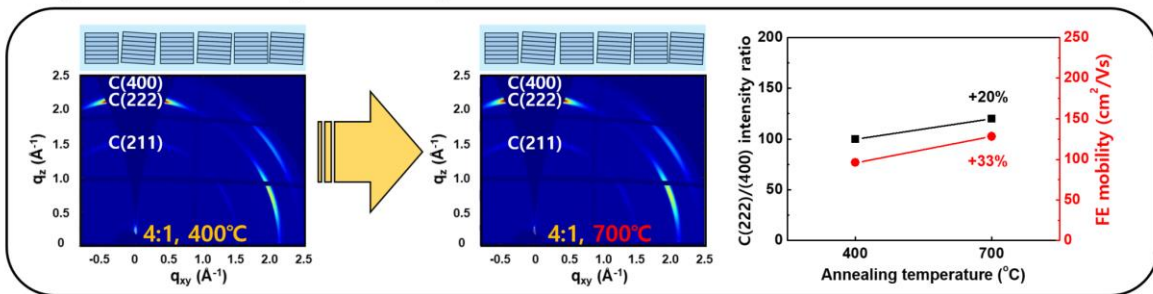


1. Optimizing ALD process for highly aligned crystalline IGO



2. High thermal stability of well-aligned IGO



3. Applicability of IGO to 3D memory device

